

N-Type Multicrystalline Silicon Solar Cells: PERC Design for High Efficiency

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Abstract: In this report, high-efficiency solar cell concepts for n-type multicrystalline silicon (mc-Si) are presented. Cells with a totally diffused and metallised Back Surface Field (BSF) reached an efficiency of 15.1% with an antireflection coating. For a further improvement of the cell efficiency the application of the PERC [1] cell design on n-type mc-Si is proposed. First PERC cells have been processed and an efficiency of 10.2% has been obtained without antireflection coating. Optimisation of this process and application of a Double Layer Antireflection Coating (DLARC) is expected to lead to efficiencies exceeding 16%.

Key Words: n-type Si, mc-Si, solar cells, PERC

1 Introduction

There are two main motivations for using n-type Si for solar cell production: the first is the shortage of the Si feedstock. As there exists a similar quantity of n-type and p-type Si scrap from the electronic industry, making n-type Si available for solar cell production would attenuate significantly the shortage. In addition, some metallurgical-grade purification processes result more easily in n-type material than in p-type [2]. The second reason is that there is growing evidence that n-type mc-Si is superior to p-type mc-Si [3, 4], since it is less sensitive to certain metallic impurities [5]. This could result in solar cells with higher efficiencies if process steps are developed and optimised for n-type mc-Si. The development of a high efficiency solar cell process for n-type mc-Si is described here.

2 Experimental Results

2.1 Cells with P-diffused BSF

It has been shown that boron emitter diffusion with BBr_3 is possible while maintaining the high starting lifetime of the n-type mc-Si material [6] and obtaining an excellent response of the IQE in the short wavelength range [7].

Small laboratory solar cells ($A = 4 \text{ cm}^2$) were made using the process depicted in Figure 1. Emitter diffusion was carried out using a BBr_3 dopant source with a subsequent thermal oxidation (an additional furnace step) and deglazing step for the removal of the boron-rich layer (BRL) that is created during boron diffusion. A BSF was formed by phosphorous ($POCl_3$) diffusion. The front grid was defined by photolithography and the contacts (Ti/Pd/Ag) on both sides were evaporated with a full rear contact. The parameters of the best solar cells resulting from this process are shown in Table I. The measured internal quantum efficiency (IQE) of the mc-cell from Table I shows an excellent response in the short wavelength range (Figure 2). In contrast to that, the long wavelength response can still be significantly improved.

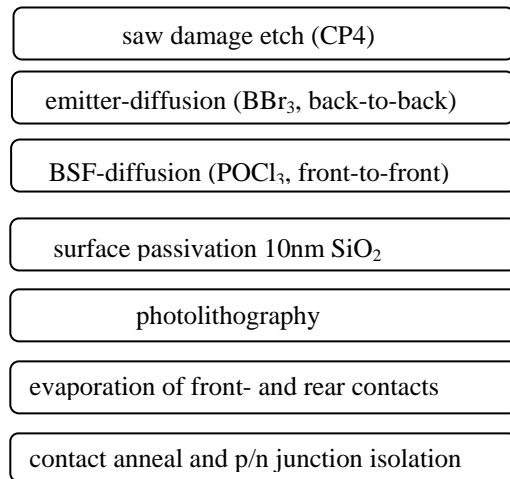


Figure 1 Solar cell process scheme

material	FF [%]	J_{sc} [mA/cm ²]	V_{oc} [mV]	η [%]
mc-Si (1 Ωcm)	78.6	23.3	603	11.0
Cz-Si (2 Ωcm)	77.9	24.4	604	11.5
	mc-cell with ARC		Cz-cell with DARC	
η [%]	15.1		16.4	

Table I Best solar cells made with with process shown in figure 1.

2.2 PERT and PERC solar cells

To improve the IQE for long wavelengths two conditions have to be fulfilled:

- 1.) the diffusion length in the bulk at the end of the cell process has to be as high as possible.
- 2.) the back surface recombination velocity has to be as low as possible.

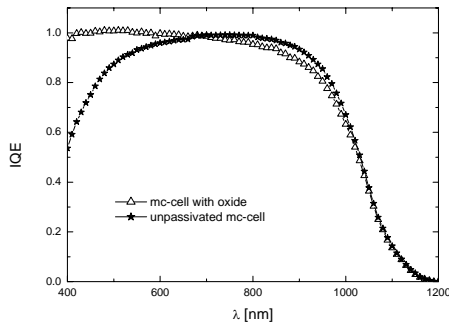


Figure 2 IQE of mc Si solar cells with passivated and unpassivated emitter.

The first condition is already met by a modification of the process in Figure 1 consisting in a BBr_3 -diffusion (back-to-back) with an in-situ oxidation of the BRL (diffusion and oxidation in one furnace step) followed by a POCl_3 -BSF diffusion (front-to-front) and the growth of a 10 nm SiO_2 -layer for front surface passivation. Figure 3 shows the largely increased lifetime after the process which corresponds to a diffusion length of the minority charge carriers exceeding 500 μm .

To meet the second condition, one can either perform a deep BSF-diffusion with POCl_3 (according to simulations with PC1D: at least 4 μm deep), a weak BSF-diffusion with SiO_2 -passivation and local metal contacts (PERT design [9]) or no BSF-diffusion at all with the SiO_2 -passivated n-type substrate and local metal contacts on the rear side (PERC design [11]). The deep POCl_3 -diffusion requires a high thermal budget and could have a detrimental effect on the bulk lifetime and thus has been omitted. Cells with PERT-structure have been processed on n-type Cz material and showed a considerable increase of the IQE for long wavelengths resulting in an increase of J_{SC} by 6.5%. First PERC-cells have been processed on 1 Ohm-cm n-type mc-Si applying the process from Figure 1 without the POCl_3 -diffusion and using point-contacts on the rear-side. The best cell reached an efficiency of 10.2% (without ARC), featuring a rather low fill factor of 70%, which is caused by the small front-grid fingers ($15 \times 3 \mu\text{m}^2$) and possibly by a non optimized rear junction geometry.

3 Conclusions and Outlook

In contrast to the BSF-cells, the PERC cells are not P-gettered. Thus, to avoid a possible degradation of the bulk lifetime by the thermal oxidation of the PERC-cells, front surface passivation by PECVD SiC_x is examined (SiN_x passivates n^+ -doped emitters of p-type cells, but depassivates the p^+ -doped emitter of the n-type cells [8]).

Further improvement of the cell efficiency is expected from the use of 0.8 Ohm-cm Si (instead of 1 Ohm-cm) and an optimisation of the rear contact geometry. In addition Ag-plating will be used to obtain a good conductivity of the front finger-grid.

Considering the 11% efficiency which has already been achieved on flat cells with full metal contact on the rear side (i.e. a high rear surface recombination velocity), we expect efficiencies of 12% from PERC-cells without ARC and exceeding 16% with a DLARC (ZnS/MgF_2).

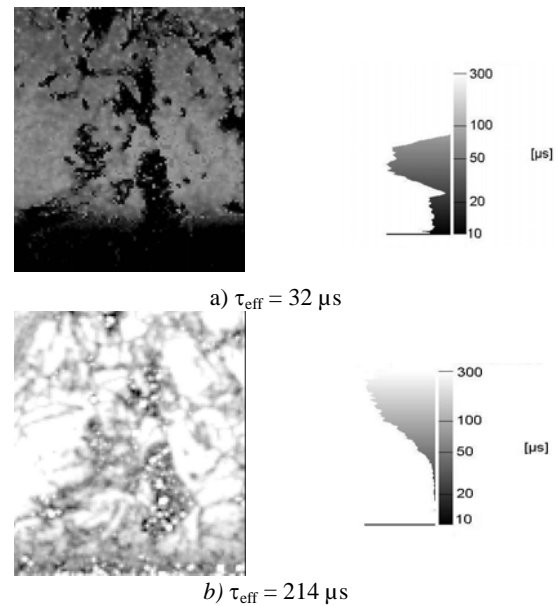


Figure 3 μW -PCD mappings of the bulk lifetime of a 10 x 12.5 cm^2 section of an n-type mc Si wafer (from the edge of the ingot): (a) before and (b) after cell process.

Diffused regions removed and surface passivated with iodine/ethanol-solution.

4 Acknowledgements

This work was supported within the NESSI project by the European Commission under contract number ENK6-CT2002-00660 and by the German BMU in the frame of the ASIS project (contract number 0329846J). The content of this publication is the responsibility of the authors.

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